

## LECTURE 170 – PASSIVE COMPONENTS IN BIPOLAR ICs (READING: Text-Sec. 2.6 and 2.7)

### INTRODUCTION

#### Objective

- Demonstrate the passive components compatible with BJT technology

#### Outline

- Resistors
- Capacitors
- High-performance active devices compatible with BJT technology

### Cross-Section of an NPN BJT

All passive components must be compatible with this structure.

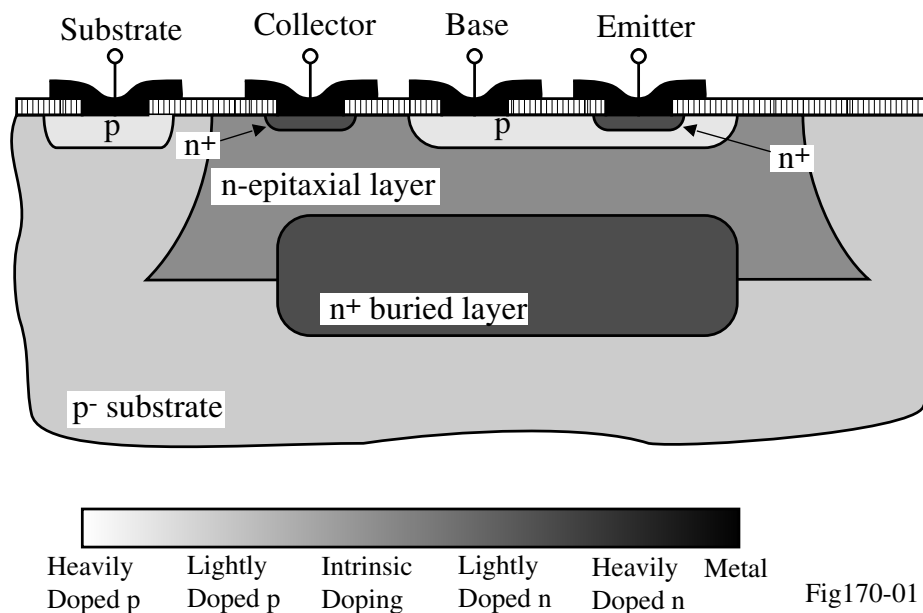
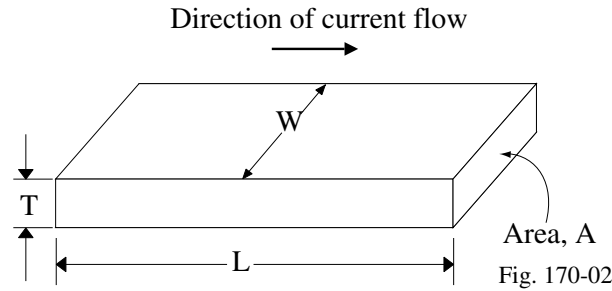


Fig170-01

## INTEGRATED CIRCUIT RESISTORS

### Resistor Layout



Resistance of a conductive sheet is expressed in terms of

$$R = \frac{\rho L}{A} = \frac{\rho L}{WT} \quad (\Omega)$$

where

$\rho$  = resistivity in  $\Omega\text{-m}$

Ohms/square:

$$R = \left(\frac{\rho}{T}\right) \frac{L}{W} = \rho_S \frac{L}{W} \quad (\Omega)$$

where

$\rho_S$  is a sheet resistivity and has the units of ohms/square

### Base and Emitter Diffused Resistors

Cross-section of a Base Resistor:

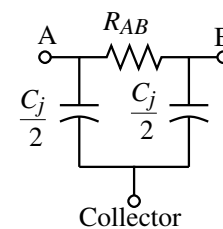
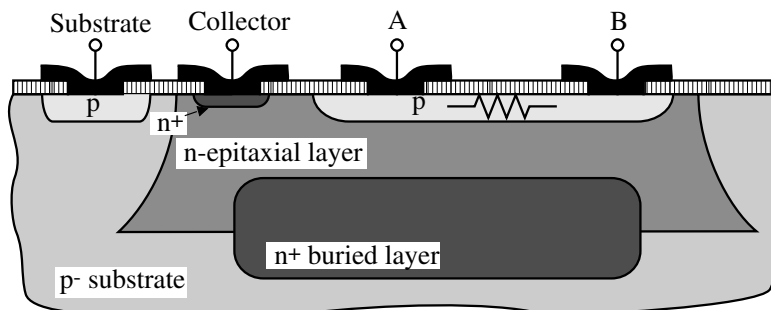


Fig. 170-03

Comments:

Sheet resistance  $\approx 100 \Omega/\text{sq.}$  to  $200 \Omega/\text{sq.}$

TCR =  $+1500\text{ppm}/^\circ\text{C}$

Note:

$$\frac{1\%}{^\circ\text{C}} = \frac{10^4}{^\circ\text{C}}$$

Emitter Resistor:

Sheet resistance  $\approx 2 \Omega/\text{sq.}$  to  $10 \Omega/\text{sq.}$  (Generally too small to make sufficient resistance in reasonable area)

TCR =  $+600\text{ppm}/^\circ\text{C}$

### Epitaxial Resistors

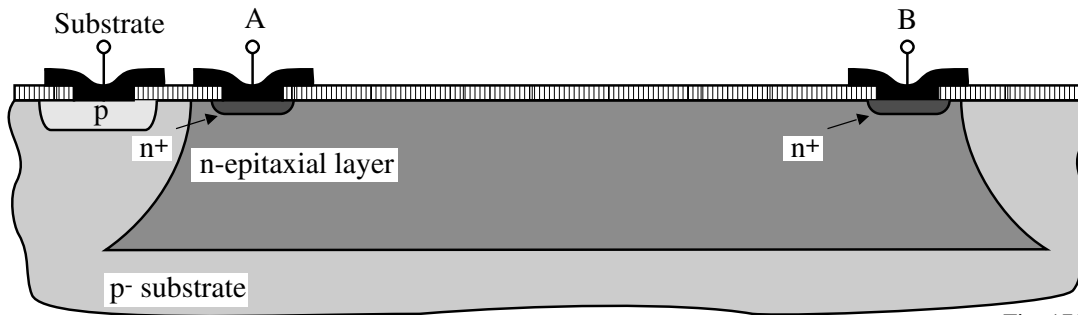


Fig. 170-04

Typical resistance is 2-5kΩ/sq.

### Epitaxial Pinched Resistor

Good for large values of sheet resistance.

Cross-section:

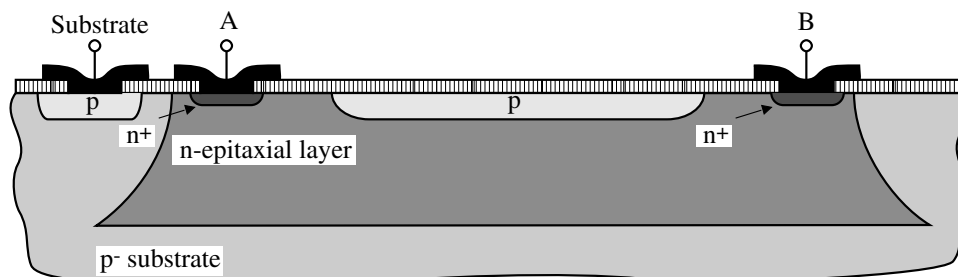


Fig 170-05

IV Curves and Model:

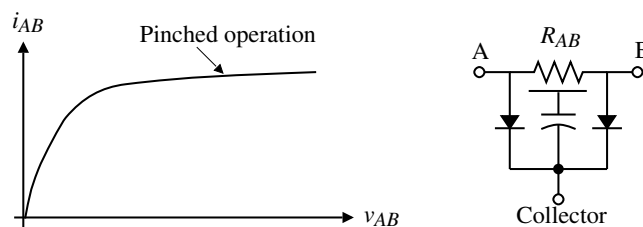


Fig. 170-06

Comments:

Sheet resistance is 4 to 10kΩ/sq.

Voltage across the resistor is limited to 6V or less because of breakdown

TCR ≈ 2500ppm/°C

### Epitaxial Pinched Resistors

Cross section:

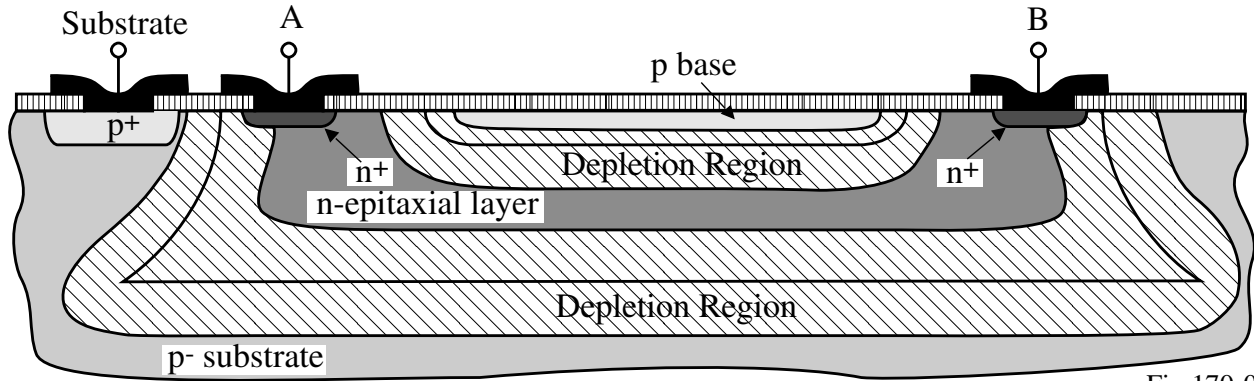


Fig 170-05

Sheet resistance  $\approx 4\text{-}10\text{k}\Omega/\text{sq.}$

Top View:

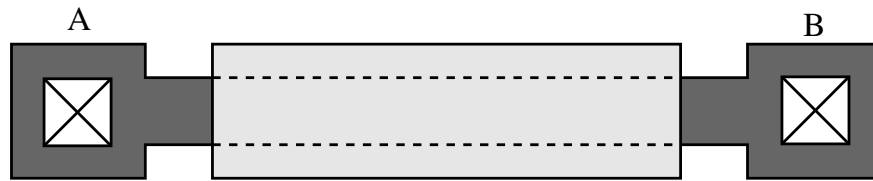


Fig 170-07

### Collector-Base Capacitance ( $C_{\mu}$ )

Illustration:

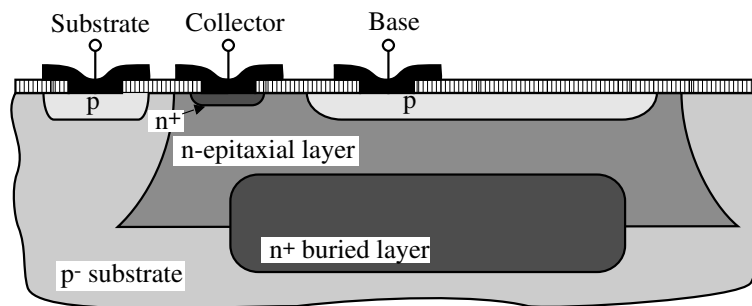


Fig. 170-08A

Model:

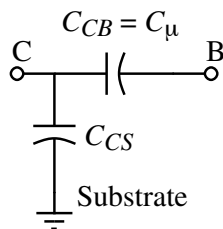


Fig 170-08B

Sidewall contribution:

$$A_{sidewall} = P \cdot d \frac{\pi}{2}$$

where

$P$  = perimeter of the capacitor

$d$  = depth of the diffusion

Values (Includes the bottom plus sidewall capacitance):

$$C_{\mu} \approx 1\text{fF}/\mu\text{m}^2 \text{ (dependent on the reverse bias voltage)}$$

Can also have base-emitter capacitance and collector-substrate capacitance

### PN Junction Capacitors

Generally made by diffusion into the well.

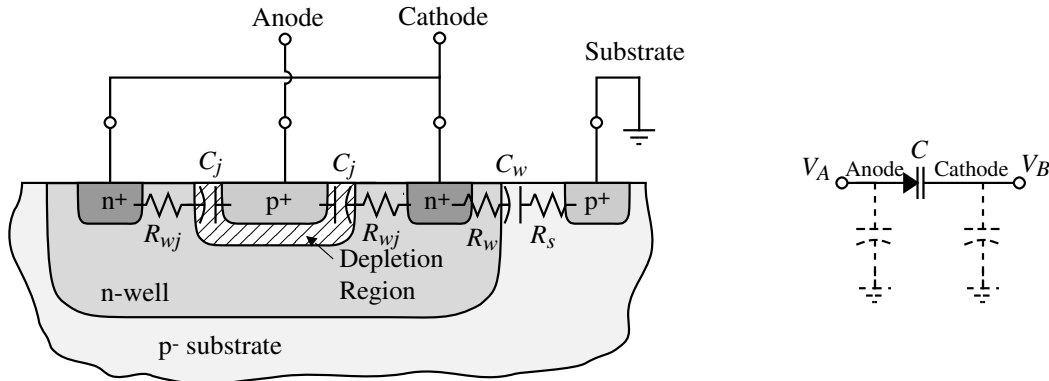


Fig. 170-09

Layout:

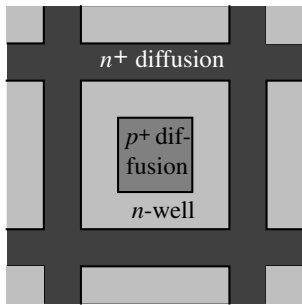


Fig. 170-10

Minimize the distance between the  $p^+$  and  $n^+$  diffusions. Two different versions have been tested.

- Large islands –  $9\mu\text{m}$  on a side
- Small islands –  $1.2\mu\text{m}$  on a side

### PN-Junction Capacitors – Continued

It can be shown that the anode should be the floating node and the cathode must be connected to ac ground.

Experimental data ( $Q$  at 2GHz,  $0.5\mu\text{m}$  CMOS):

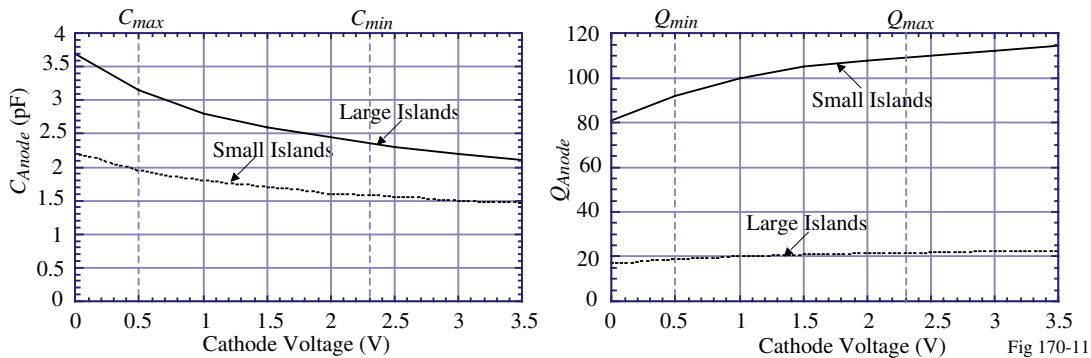


Fig 170-11

Summary:

Terminal Under Test	598 $1.2\mu\text{m} \times 1.2\mu\text{m}$ islands			42 $9\mu\text{m} \times 9\mu\text{m}$ islands		
	$C_{max}/C_{min}$	$Q_{min}$	$Q_{max}$	$C_{max}/C_{min}$	$Q_{min}$	$Q_{max}$
Anode	1.23	94.5	109	1.32	19	22.6
Cathode	1.21	8.4	9.2	1.29	8.6	9.5

Electrons as majority carriers lead to higher  $Q$  because of their higher mobility. Also, the resistance,  $R_{wj}$ , is reduced in the small islands compared with the large islands giving higher  $Q$ .

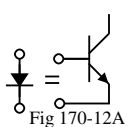
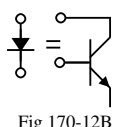
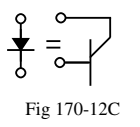
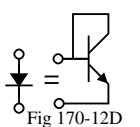
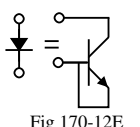
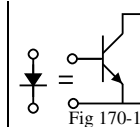
## Integrated Circuit Passive Component Performance Summary

Component Type	Range of Values	Absolute Accuracy	Relative Accuracy	Temperature Coefficient	Voltage Coefficient
Base Diffused	100-200 $\Omega$ /sq.	$\pm 20\%$	0.2%	+1750ppm/ $^{\circ}$ C	-
Emitter Diffused	2-10 $\Omega$ /sq.	$\pm 20\%$	$\pm 2\%$	+600ppm/ $^{\circ}$ C	-
Epitaxial	2k-5k $\Omega$ /sq.	$\pm 50\%$	$\pm 10\%$	+2500ppm/ $^{\circ}$ C	Poor
Epitaxial Pinched	4k-10k $\Omega$ /sq.	$\pm 50\%$	$\pm 7\%$	+3000ppm/ $^{\circ}$ C	Poor
Thin Film	0.1k-2k $\Omega$ /sq.	$\pm 5$ - $\pm 20\%$	$\pm 0.2$ - $\pm 2\%$	$\pm 10$ to $\pm 200$ ppm/ $^{\circ}$ C	-

## DIODES

### BJT Diode

Different configurations

Diode	 Fig 170-12A	 Fig 170-12B	 Fig 170-12C	 Fig 170-12D	 Fig 170-12E	 Fig 170-12F
Condition	$I_C = 0$	$I_E = 0$	$I_E = 0$ no emitter	$V_{CB} = 0$	$V_{EB} = 0$	$V_{CE} = 0$
Series Resistance	$r_{bb}'$	$r_{bb}' + r_{cc}'$	$r_{bb}' + r_{cc}'$	$r_{bb}'/\beta$	$r_{bb}'/\beta + r_{cc}'$	$r_{bb}'$
$V_F$ @ 10mA	960mV	950mV	950mV	850mV	940mV	920mV
Breakdown Voltage	$BV_{EBO}$	$BV_{CBO}$	$BV_{CBO}$	$BV_{EBO}$	$BV_{CBO}$	$BV_{EBO}$
Storage Time	$\approx 70$ ns	$\approx 130$ ns	$\approx 80$ ns	$\approx 6$ ns	$\approx 90$ ns	$\approx 150$ ns

Base-collector shorted BJT is the most attractive diode for most applications.

## Dielectric Isolation

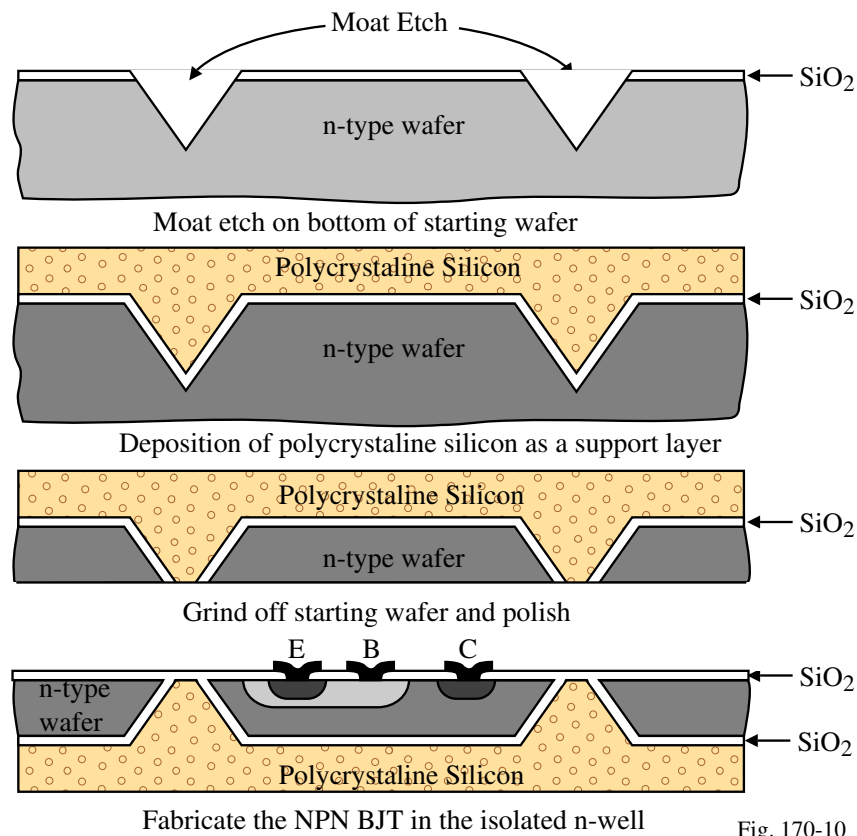


Fig. 170-10

## Compatible High-Performance Transistors

- **Superbeta transistors**  
Allow the emitter diffusion to almost reach the collector side of the base creating a very small base width. Reduces the breakdown voltage but increases  $\beta$  to as much as 2000 to 5000.
- **p-channel MOS transistor**  
Use the base diffusions to create the source and drain in an n-epitaxial island and thin oxide and metal to form the gate.
- **Double-diffused pnp transistors**  
Diffuse a p collector into the n-epitaxial region along with a n-diffusion for the base and a heavily doped p diffusion for the emitter.

## **SUMMARY**

- Showed passive components that were compatible with bipolar IC technology
- Capacitors use pn-junctions and are depletion capacitors
- Resistors include:
  - Base/emitter diffused
  - Epitaxial
  - Epitaxial pinched
- Diodes
  - Base-collector shorted diode is the best choice for most applications
- Modifications to the standard bipolar technology include:
  - Dielectric isolation
  - High-performance transistors